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APPLICATION NO.	FI	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/825,087	04/02/2001		Cem Basceri	MI22-1483	1701
21567	7590	09/10/2004		EXAMINER	
WELLS ST			TALBOT, BRIAN K		
601 W. FIRST AVENUE, SUITE 1300 SPOKANE, WA 99201				ART UNIT	PAPER NUMBER
				1762	

DATE MAILED: 09/10/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
	09/825,087	BASCERI ET AL.					
Office Action Summary	Examiner	Art Unit					
	Brian K Talbot	1762					
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address					
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days rill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).					
Status							
1) Responsive to communication(s) filed on 23 Ju	ıne 2004.						
	action is non-final.						
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims							
<ul> <li>4)  Claim(s) 1-21 and 40-58 is/are pending in the at 4a) Of the above claim(s) is/are withdraw</li> <li>5)  Claim(s) 55-58 is/are allowed.</li> <li>6)  Claim(s) 1-21 and 40-54 is/are rejected.</li> <li>7)  Claim(s) is/are objected to.</li> <li>8)  Claim(s) are subject to restriction and/or</li> </ul>	vn from consideration.						
Application Papers							
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) access applicant may not request that any objection to the objection to the object of the control of the object o	epted or b) objected to by the Eddrawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).					
		7.6.6.7.6.7.7.7.7.7.7.7.7.2.					
Priority under 35 U.S.C. § 119  12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list of the certified copies of the attached detailed Office action for a list of the certified copies of the attached detailed Office action for a list of the certified copies of the priorical supplication from the International Bureau * See the attached detailed Office action for a list of the certified copies of the priorical supplication from the International Bureau * See the attached detailed Office action for a list of the priorical supplication from the International Bureau * See the attached detailed Office action for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical supplication from the International Section for a list of the priorical section for a list of the pri	s have been received. s have been received in Application ity documents have been receive I (PCT Rule 17.2(a)).	on No ed in this National Stage					
Attachment(s)  1) X Notice of References Cited (PTO-892)	4\ ☐ Interview Com	(PTO.413)					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4) ☐ Interview Summary Paper No(s)/Mail Da	ate					
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 6/23/04.	5)  Notice of Informal P 6)  Other:	atent Application (PTO-152)					

Page 2

Application/Control Number: 09/825,087

Art Unit: 1762

#### Continued Examination Under 37 CFR 1.114

- 1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 6/23/04 has been entered.
- 2. Claims 1-21 and 40-58 remain in the application.
- 3. In light of the response filed 6/23/04, the 35 USC 112 second paragraph rejection of claim 56 has been withdrawn.
- 4. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.

#### Allowable Subject Matter

5. Claims 55-58 are allowable.

The following is a statement of reasons for the indication of allowable subject the prior art fails to teach or fairly suggest forming capacitor-to-plate dielectric interface comprising a first

Application/Control Number: 09/825,087 Page 3

Art Unit: 1762

capacitor plate of Pt or Ru on a semiconductive substrate, an interface layer consisting of the claims materials formed by chemisorption on the first capacitor plate and a second capacitor plate atop the interface layer.

## Claim Rejections - 35 USC § 103

6. Claims 1-21 and 40-54 are rejected under 35 U.S.C. 103(a) as being unpatentable over Suntola et al. (4,058,430) (a) alone or (b) in combination with Yu et al. (6,241,821 B1) or Marscher (4,109,031).

Suntola et al. (4,058,430) teaches forming a compound film whereby a substrate is subjected to a vapor of a first element at a temperature to form a single atomic layer thereon, the a vapor of a second element is introduced to form a second atomic layer atop the first atomic layer. This is repeated until a desired thickness is achieved and then the layers are heated to form the compound film (see abstract and col. 6 - col. 7). Suntola et al. (4,058,430) teaches partial coverage can be achieved of the first element on the substrate and then forming the second element (col. 9, lines 20-60 and claim 7).

Suntola et al. (4,058,430) fails to teach forming a first element layer and a second element layer surrounding or sandwiching the compound layer (interlayer).

(a) While the Examiner acknowledges the fact that the reference is silent upon forming the compound layer between two layers, it is the Examiner's position that one skilled in the art at the time the invention was made would have had a reasonable expectation of achieving similar

Application/Control Number: 09/825,087

Art Unit: 1762

results regardless of whether or not the compound layer was formed on a substrate or on a deposited film.

(b) Yu et al. (6,241,821 B1) teaches forming single atomic layer interface layers between two layers. The interface layer can be comprised of Si, O, and a metal. A layer of BaO or SrO can be applied to a substrate prior to the interface layer being applied thereto and a subsequent layer can be applied to the interface layer. The interface layer is applied by chemisorption. (col. 2, line 15 – col. 4, line 40).

Marscher (4,109,031) teaches forming gradient layer between metal and ceramic layers which are comprised of 100% metal adjacent the metal to 100% ceramic with variations throughout the interlayer with an increase in ceramic material the more further away from the metal (col. 1, lines 10-30 and col. 2, lines 22-60). While the Examiner acknowledges the fact that Marscher (4,109,031) does not disclose chemisorption for the depositing layers, it is the Examiner's position that the use of gradient layer between different materials to alleviate the differences in thermal expansion/stresses upon subsequent heating would be achieved regardless of what technique was utilized to form the layers. In addition, some of the claims recite the first material being metal (Pt or Ru) and the second material being a metal oxide (TaO or titanates) which are similar to the materials disclosed in Marscher (4,109,031).

Therefore, it would have been obvious at the time the invention was made to have modified Suntola et al. (4,058,430) process by performing the chemisorption layer between layers as evidenced by Yu et al. (6,241,821 B1) because of the expectation of achieving similar success.

Application/Control Number: 09/825,087

Art Unit: 1762

7. Claims 1-21 and 40-54 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lim et al (6,570,253).

Lim et al (6,570,253) teaches a multi-layer film for capacitor structures. A multi-layer film includes a compositional transition layer between a lower material layer and an upper material layer formed of different materials. The compositional transition layer comprise materials form both the first and second layers (abstract). The compositional transition layer can be more than one layer depending upon the cycling of the reaction deposition process (col. 7, lines 20-35 and Figs. 6,7).

Lim et al (6,570,253) fails to teach that the transitional layer improves adhesion between the first and second layers.

While Lim et al (6,570,253) fails to explicitly teach an improvement in adhesion, it is the Examiner's position, that not only would there be an improvement in adhesion between the layers the use of gradient layers is well known to alleviate the differences in thermal expansion/stresses upon subsequent heating would be achieved regardless of what technique was utilized to form the layers.

### Response to Amendment

8. Applicant's arguments filed 6/23/03 have been fully considered but they are not persuasive.

Art Unit: 1762

9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Brian K Talbot whose telephone number is (571) 272-1428. The examiner can normally be reached on Monday-Friday 6AM-3PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Shrive P Beck can be reached on (571) 272-1415. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Brian K Talbot Primary Examiner Art Unit 1762

& Kralls

**BKT**